IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

Peter J. Zdebel

FILED:

Concurrently Herewith

FOR:

HIGH ENERGY ESD STRUCTURE AND METHOD

Date:

12/29/2003

DISCLOSURE STATEMENT UNDER 37 C.F.R. 1.56

Honorable Assistant Commissioner for Patents Washington, D.C. 20231

SIR:

It is respectfully requested that the prior art listed on FORM PTO-1449 be considered in the examination of the subject application and made of record therein. A copy of the listed prior art is enclosed herewith.

No representation is made or intended that the listed prior art enclosed herewith is material to patentability of the subject patent application.

No representation is made or intended that a search has been made or that no better prior art than that listed is available.

Respectfully submitted,

Peter J. Zdebel et al

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Form PTO- 1449	ATTY. DOCKET NO.	SERIAL NO.			
LIST OF PATENTS AND PUBLICATIONS FOR	Ons00535				
APPLICANT'S INFORMATION DISCLOSURE	APPLICANT Peter Zdebel et al				
STATEMENT	FILING DATE	GROUP			
(Use Several Sheets if Necessary)	Concurrently				
	herewith				

REFERENCE DESIGNATION **U.S. PATENT DOCUMENTS** DOCUMENT CLASS | SUBCLASS | FILING DATE **EXAMINER** INITIAL NUMBER DATE NAME IF APPROPRIATE AA AB AC AD ΑE AF AG AH ΑI AJ AK AL

FOREIGN PATENT DOCUMENTS

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EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.